

Air stable n-type black phosphorus transistor with photoactive doping layer

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Abstract

Black phosphorus (BP) is usually a p-type semiconductor with hole mobility of its device range from $100\text{cm}^2\text{V}^{-1}\text{s}^{-1}$ to $300\text{cm}^2\text{V}^{-1}\text{s}^{-1}$ and on/off ratio up to 10^5 . However, BP is very sensitive to the environment and its outstanding properties will fade away in a short time under moisture and oxygen exposure.

In this presentation, a novel approach to demonstrate tunable transport properties of a few-layered BP field-effect transistor (FET) device with extended air stability will be proposed. With Titanium suboxide (TiO_x) thin film applied on BP surface we can not only improve its air stability but also provide tunable n-type doping on BP through light illumination which can modify the transport properties of BP from the intrinsic hole-dominated transport to the electron-dominated transport. With controllable transport properties on channel, this novel device structure of BP exhibit great potential for the future development of logic devices or optoelectronic devices.[1]

References

- [1] P.H. Ho et al., ACS photonics, Vol.3 issue6 (2016) pp1102–1108

Figures

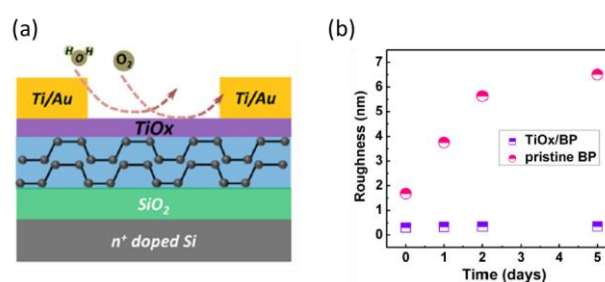


Figure 1: (a) Schematic representation of a BP FET with precoated TiO_x layer. (b) Time-dependent evolution of surface roughness of BP with and without coating TiO_x film.

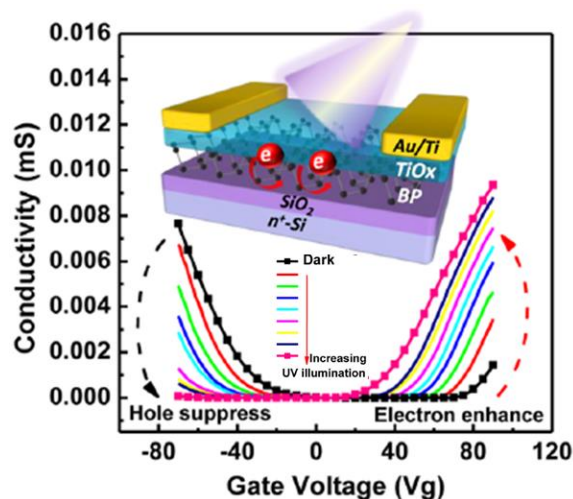


Figure 2: Evolution of conductivity versus gate-voltage curves for the TiO_x/BP FET with increased irradiation time. The inset is the schematic representation of a BP/TiO_x transistor under illumination